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METHOD FOR MANUFACTURE OF MAGNETO-RESISTIVE BIT
STRUCTURE

Liu et al.

Appl. No.: Unknown

Atty Docket: MICRON.230C1

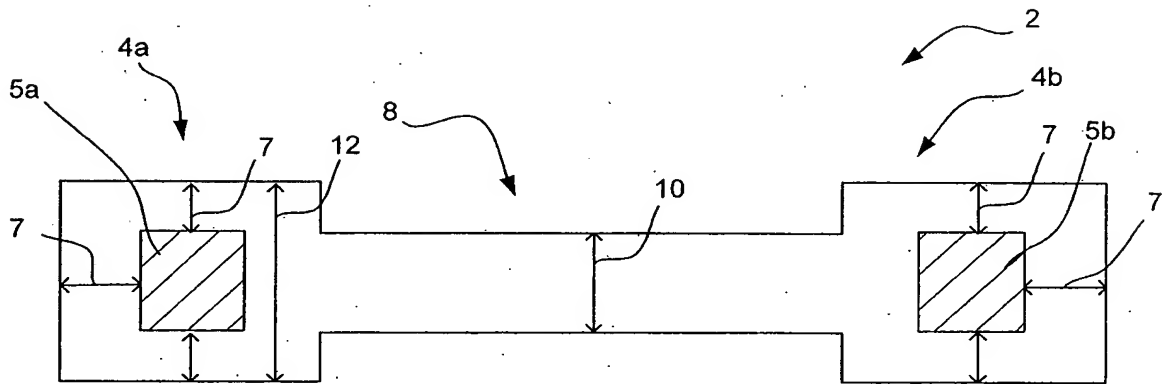


FIG. 1

METHOD FOR MANUFACTURE OF MAGNETO-RESISTIVE BIT
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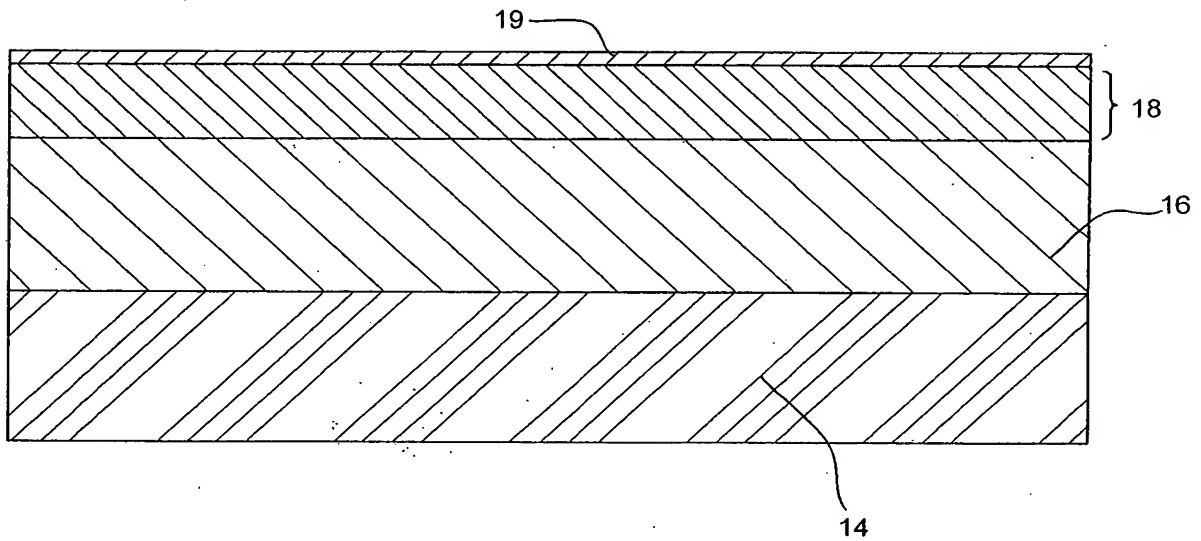


FIG. 2

METHOD FOR MANUFACTURE OF MAGNETO-RESISTIVE BIT
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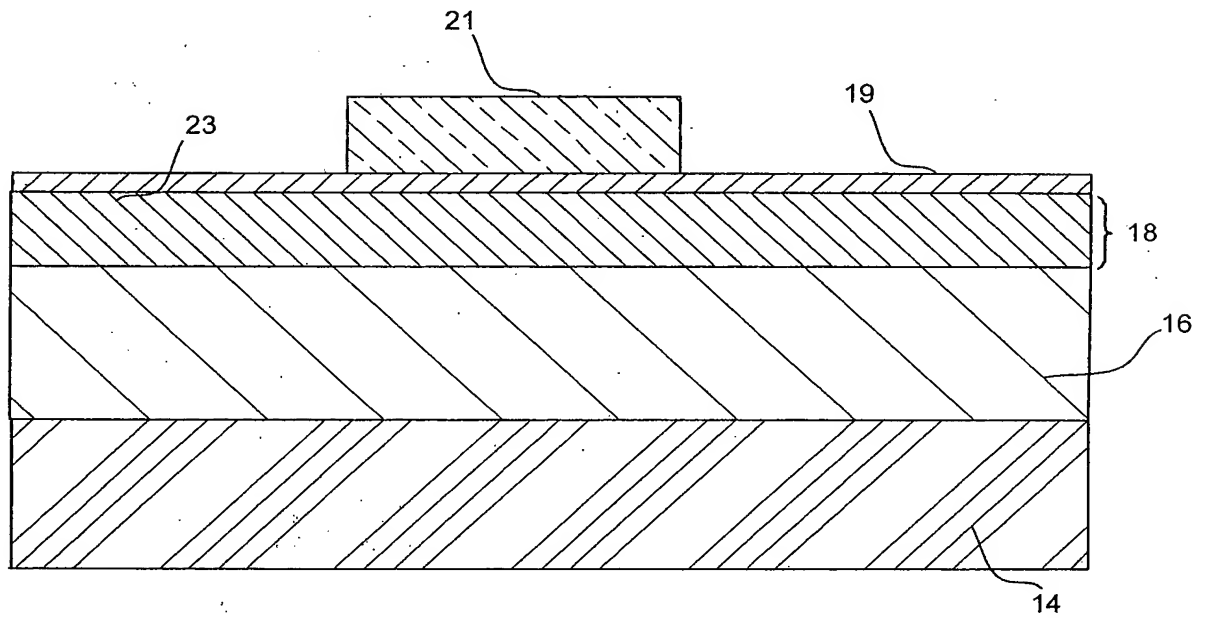


FIG. 3

METHOD FOR MANUFACTURE OF MAGNETO-RESISTIVE BIT
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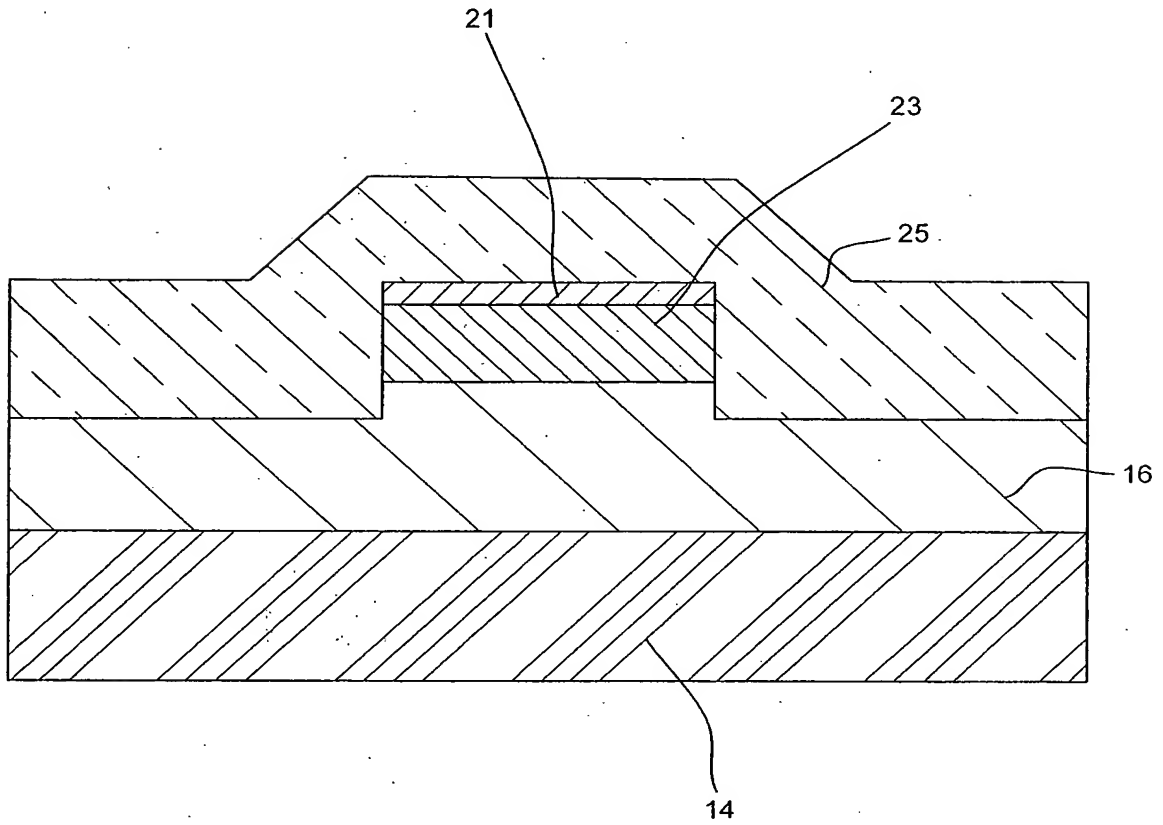


FIG. 4

METHOD FOR MANUFACTURE OF MAGNETO-RESISTIVE BIT
STRUCTURE

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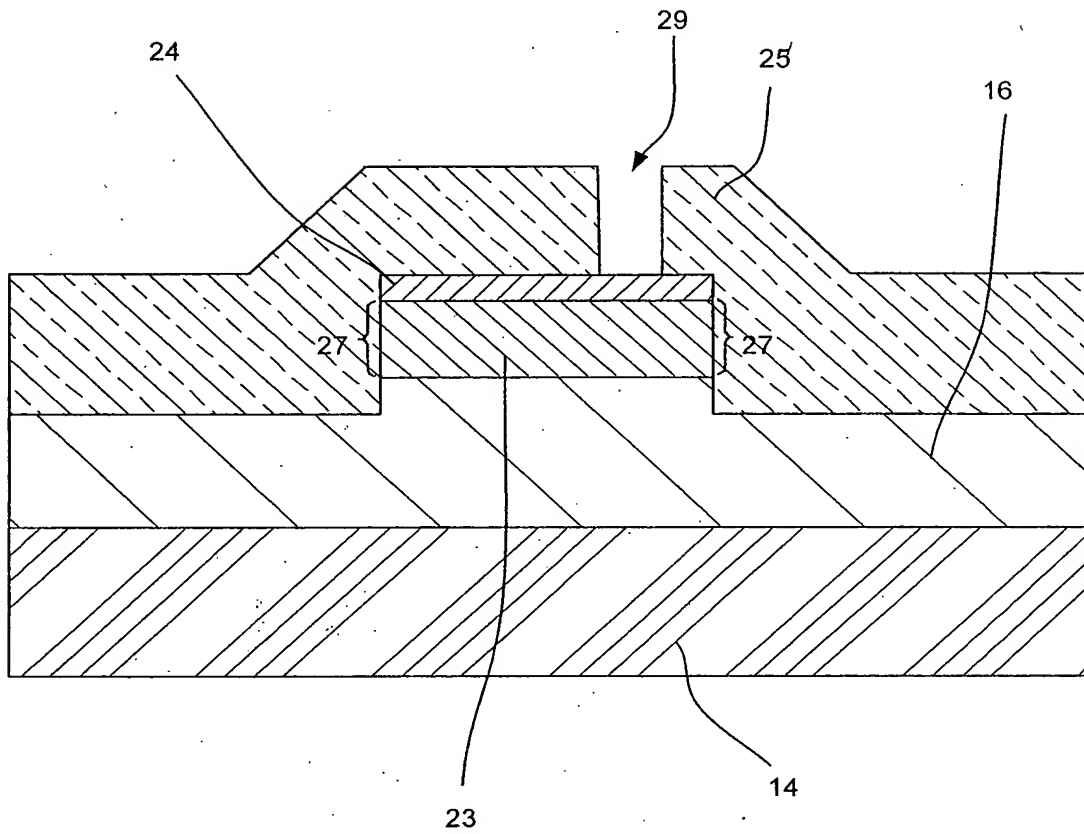


FIG. 5

METHOD FOR MANUFACTURE OF MAGNETO-RESISTIVE BIT
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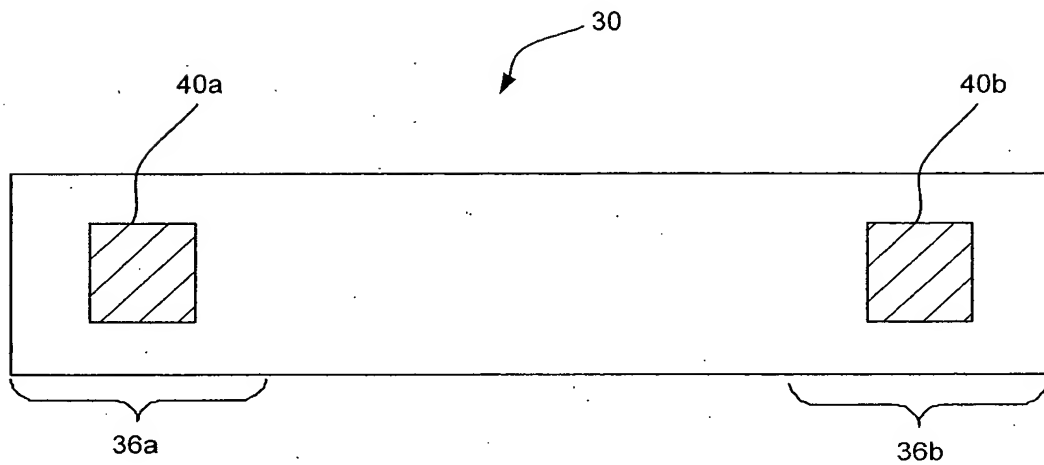


FIG. 6